

**METHOD OF FORMING MULTI-LAYERS FOR A THIN FILM TRANSISTOR
(TFT) THE DEVICE FORMED THEREBY**

ABSTRACT OF THE DISCLOSURE

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The present invention concerns a method of forming multi-layers such as base-coat and active layers for TFTs. In accordance with the preferred embodiment of the present invention, a first layer is formed on a transparent substrate using a physical vapor deposition. And a second layer is sequentially formed using a physical vapor deposition on the first layer without breaking vacuum.

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The present invention simplifies the TFT fabrication while decreasing the water or hydrogen content within multilayers including a base-coat (BC) layer.

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